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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/530,063	03/31/2005	Philippe Meunier-Beillard	BE02 0027 US	6267
65913 <b>NXP, B.V</b> .	7590 06/16/200	Philippe Meunier-Beillard	EXAMINER	
NXP INTELLECTUAL PROPERTY DEPARTMENT			ESTRADA, MICHELLE	
	M/S41-SJ 1109 MCKAY DRIVE			PAPER NUMBER
SAN JOSE, CA 95131		2823		
			NOTIFICATION DATE	DELIVERY MODE
			06/16/2008	ELECTRONIC

## Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Notice of the Office communication was sent electronically on above-indicated "Notification Date" to the following e-mail address(es):

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		Application No.	Applicant(s)			
Office Action Summary		10/530,063	MEUNIER-BEILLARD ET AL.			
		Examiner	Art Unit			
		Michelle Estrada	2823			
Period fo	The MAILING DATE of this communication app or Reply	pears on the cover sheet with the o	correspondence address			
WHIC - Exte after - If NC - Failu Any	ORTENED STATUTORY PERIOD FOR REPL' CHEVER IS LONGER, FROM THE MAILING DA asions of time may be available under the provisions of 37 CFR 1.1 SIX (6) MONTHS from the mailing date of this communication. by period for reply is specified above, the maximum statutory period of the reply within the set or extended period for reply will, by statute reply received by the Office later than three months after the mailing and patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be tirwill apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	N. nely filed the mailing date of this communication. D (35 U.S.C. § 133).			
Status						
1) 又	Responsive to communication(s) filed on <u>11 M</u>	larch 2008				
-		action is non-final.				
3)	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
٥/ك	closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
Disposit	on of Claims					
4)⊠	)⊠ Claim(s) <u>4,5,7,18,19,21 and 22</u> is/are pending in the application.					
-	4a) Of the above claim(s) is/are withdrawn from consideration.					
	☐ Claim(s) <u>5,19,21 and 22</u> is/are allowed.					
·	)⊠ Claim(s) <u>4,7 and 18</u> is/are rejected.					
	Claim(s) is/are objected to.					
-	Claim(s) are subject to restriction and/o	r election requirement.				
	ion Papers	·				
•	9) The specification is objected to by the Examiner. 10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.					
10)[						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).  11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.						
	ınder 35 U.S.C. § 119					
<ul> <li>12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).</li> <li>a) All b) Some * c) None of:</li> <li>1. Certified copies of the priority documents have been received.</li> <li>2. Certified copies of the priority documents have been received in Application No</li> <li>3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).</li> <li>* See the attached detailed Office action for a list of the certified copies not received.</li> </ul>						
2) Notice (3) Inform	t(s) se of References Cited (PTO-892) se of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO/SB/08) r No(s)/Mail Date	4)  Interview Summary Paper No(s)/Mail D 5)  Notice of Informal F 6)  Other:	ate			

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## **DETAILED ACTION**

## Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 4, 7 and 18 rejected under 35 U.S.C. 103(a) as being unpatentable over Shiota et al. (5,879,970) in view of the following comments.
- 3. Shiota et al. discloses depositing an epitaxial layer based on Group IV elements a silicon substrate by Chemical Vapor Deposition using source gases (See abstract), and including employing nitrogen as a carrier gas, wherein the epitaxial layer comprises a SiGe epitaxial layer (Abstract and Col.6, lines 15-20). Shiota discloses wherein the method is carried out at a temperature between 350 °C and 450 °C.
- 4. Shiota does not specifically disclose wherein the method is carried out at a temperature between 500 °C and 600 °C. However, the recited range and the one disclosed by Shiota is close enough to be considered routine optimization.
- 5. One of ordinary skill in the art would have been to the recited temperature through routine experimentation to achieve a desired rate of deposition.

In addition, the selection of temperature, it's obvious because it is a matter of determining optimum process conditions by routine experimentation with a limited number of species of result effective variables. These claims are prima facie obvious without showing that the claimed ranges achieve unexpected results relative to the prior

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art range. In re Woodruff, 16 USPQ2d 1935, 1937 (Fed. Cir. 1990). See also In re Huang, 40 USPQ2d 1685, 1688 (Fed. Cir. 1996)(claimed ranges or a result effective variable, which do not overlap the prior art ranges, are unpatentable unless they produce a new and unexpected result which is different in kind and not merely in degree from the results of the prior art). See also In re Boesch, 205 USPQ 215 (CCPA) (discovery of optimum value of result effective variable in known process is ordinarily within skill or art) and In re Aller, 105 USPQ 233 (CCPA 1995) (selection of optimum ranges within prior art general conditions is obvious).

Note that the specification contains no disclosure of either the critical nature of the claimed temperature or any unexpected results arising therefrom. Where patentability is said to be based upon particular chosen temperature or upon another variable recited in a claim, the Applicant must show that the chosen temperature are critical. In re Woodruf, 919 F.2d 1575, 1578, 16 USPQ2d 1934, 1936 (Fed. Cir. 1990).

Re claim 7, Shiota et al. disclose wherein the CVD process is carried out at a temperature that facilitates a CVD growth rate of an epitaxial layer that is substantially greater than a CVD growth rate of such an epitaxial layer using hydrogen as a carrier gas, since the same temperature is being used as the present invention (less than 600 °C).

Re claim 18, the Examiner takes official notice that the use of SiH<sub>4</sub> and GeH<sub>4</sub> as source gases to form an epitaxial SiGe layer was known at the time of Applicant's invention. Therefore, it would have been obvious to one of ordinary skill in the art to use Art Unit: 2823

the known gases to grow a SiGe layer in the process of Shiota in the search for

alternate suitable materials.

Allowable Subject Matter

6. Claims 5, 19, 21 and 22 are allowed.

Conclusion

7. Applicant's amendment necessitated the new ground(s) of rejection presented in

this Office action. Accordingly, THIS ACTION IS MADE FINAL. See MPEP

§ 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37

CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE

MONTHS from the mailing date of this action. In the event a first reply is filed within

TWO MONTHS of the mailing date of this final action and the advisory action is not

mailed until after the end of the THREE-MONTH shortened statutory period, then the

shortened statutory period will expire on the date the advisory action is mailed, and any

extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of

the advisory action. In no event, however, will the statutory period for reply expire later

than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Michelle Estrada whose telephone number is 571-272-

1858. The examiner can normally be reached on Monday through Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Matthew Smith can be reached on 571-272-1907. The fax phone number

for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the

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/Michelle Estrada/ Primary Examiner, Art Unit 2823

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June 9, 2008